Growth of Fe4N/Cu/Fe4N tri-layer structure for current-perpendicular-to-plane giant magnetoresistance devices Institute for Materials Research, Tohoku Univ. ¹, CSRN, Tohoku Univ. ² °Keita Ito^{1,2}, Takahide Kubota^{1,2}, Koki Takanashi^{1,2}

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Anti-perovskite type 3d transition metal ferromagnetic nitrides are promising candidates for a new spintronics material. Fe_4N , one of these compounds, is theoretically predicted to have a large negative spin-polarization of electrical conductivity ($P_{\sigma} = -1.0$) [1]. In addition, a large tunnel magnetoresistance effect is theoretically expected due to coherent tunneling in a Fe₄N/MgO/Fe₄N magnetic tunnel junction with perpendicular magnetic anisotropy [2], and voltage control of magnetocrystalline anisotropy in Fe₄N/MgO is predicted by theoretical calculations [3]. On the other hand, we consider that the large $|P_{\sigma}|$ relatively high electrical resistivity of Fe₄N suitable and are for application to а current-perpendicular-to-plane giant magnetoresistance (CPP-GMR) recording head of a next generation hard disk drive [4]. In this work, we grew Fe₄N/Cu/Fe₄N tri-layer structure by molecular beam epitaxy toward fabrication of Fe₄N-based CPP-GMR devices.

Fe₄N(20 nm)/Cu(5 nm)/Fe₄N(7 nm)/Au(7 nm) layered structure was grown on a SrTiO₃(STO)(001) single crystal substrate. The top and bottom Fe₄N layers were grown at 450 °C by supplying Fe and radio-frequency N₂ plasma, simultaneously. The Cu spacer and Au capping layers were formed at room temperature. The grown layered sample was characterized by reflection high-energy electron diffraction (RHEED) and out-of-plane (ω -2 θ) x-ray diffraction (XRD).

Figure 1 shows the RHEED patterns during the growth of the sample. Streaky patterns are observed in each layer. Figure 2 shows the ω -2 θ XRD pattern of the sample, and the diffraction peaks of Fe₄N 001, 002, and Cu 002 are clearly observed. From these results, the epitaxial growth of Fe₄N/Cu/Fe₄N structure on STO(001) is confirmed. As a next step, we are trying to grow the Fe₄N/Cu/Fe₄N tri-layer structure on a thick Cu₃Au metallic buffer layer, and fabricate CPP-GMR devices, the results of which will be shown in the presentation.

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Fig. 1 RHEED patterns of the sample.



Fig. 2 The ω -2 θ XRD pattern of the sample.